NANOCHEM®

WK-Series (White Knight™) Gas Purifiers

Overview

NANOCHEM® WK-Series (White Knight™) purifiers offer the highest lifetimes and the best impurity removal efficiencies in a very economical design. The in-line design enables a very compact footprint and allows drop-in replacement of competing hardware designs. The WK-Series is available in a number of sizes for point-of-use applications to bulk gas purification.

Features and Benefits

- For point-of-use to bulk flow specialty gas purification
- **Highest Lifetimes**
- **Best Impurity Removal Efficiencies**
  - Removes critical contaminants to sub part-per-trillion levels
- Enhances manufacturing process economy and improves equipment performance
- Provides consistently high purity gas under fluctuating inlet impurity conditions
- Improves component lifetime and reduces particle generation by removing moisture from corrosive gases
- Compact footprint; inline design
- Easy to install and operate
- No heating or cooling required
- Quick start up
- All metal parts, type 316L stainless steel, or Nickel 200
- Economical, low cost of ownership

Impurities Removed

Gas Type	Contaminants	Outlet Purity
Inerts - Nitrogen (N_2), Argon (Ar), other inerts	H_2O	< 86 ppt
	O_2	< 50 ppt
	CO	< 100 ppt
	CO_2	< 24 ppt
	Benzene	< 156 ppq
	Toluene	< 93 ppq
	Ethylbenzene	< 96 ppq
	m,p-Xylene	< 79 ppq
	o-Xylene	< 112 ppq
	Refractories*	< 134 ppq
	H_2	< 1 ppb
Ammonia (NH_3)	H_2O	< 45 ppb
	O_2	< 0.1 ppb
	CO_2	< 11 ppb
	Carbamate	< 11 ppb
	GeH_4	< 1 ppb
	SiH_4	< 3 ppb
	Siloxanes	< 40 ppb
	Metals	
	Al	< 0.6 ppb
	Cu	< 0.27 ppb
	Fe	< 0.8 ppb
	K	< 0.35 ppb
	Na	< 0.27 ppb
	Si	< 1.3 ppb
	W	< 0.11 ppb
	Zn	< 0.27 ppb
	Zr	< 0.11 ppb
	Hydrocarbons from Liquid NH_3	
	Napthenic and Paraffins	85% removal
	Ethyl Benzene	96% removal
	Dissolved other HC	<200 ppb
	Hydrocarbons from Gaseous NH_3	
	n-Butane	< 30 ppb
	Ethylbenzene	< 30 ppb
Carbon Dioxide (Purifier material HCX)	Isopropyl Alcohol	< 200 ppt
	Acetone	< 93 ppt
	Propene	< 1 ppt
	Ethanol	< 1 ppt
	Carbon Disulfide	< 1 ppt
	Hexane	< 1 ppt
	Benzene	< 1 ppt

Gas Type	Contaminants	Outlet Purity
Carbon Dioxide (Purifier material HCX) *continued*	Heptane	< 1 ppt
	Toluene	< 1 ppt
	m,p-Xylene	< 1 ppt
	o-Xylene	< 1 ppt
	Ethyl Toluene	< 1 ppt
	1,3,5-Trimethyl Benzene	< 1 ppt
	1,2,4-Trimethyl Benzene	< 1 ppt
	DichloroBenzene	< 1 ppt
Silane (SiH_4)	H_2O	< 100 ppt
	O_2	< 100 ppt
	CO_2	< 100 ppt
	CO**	< 1 ppb
	Chlorosilanes, disilane, siloxanes, arsine, phosphine	
Hydrogen (H_2)	H_2O	< 100 ppt
	O_2	< 100 ppt
	CO_2	< 100 ppt
Methane (CH_4)	CO**	< 1 ppb
Ethane (C_2H_6), other HC	NOx, SOx, H2S	
Sulfur Hexafluoride (SF_6)	H_2O in inert gas	< 100 ppt
	O_2 in inert gas	< 100 ppt
	CO_2 in inert gas	< 100 ppt
Carbon Tetrafluoride (CF_4)	H_2O in sulfur hexafluoride	< 10 ppb
	O_2 in sulfur hexafluoride	< 10 ppb
Other Fluorocarbons	H_2O in sulfur hexafluoride	< 10 ppb
	O_2 in sulfur hexafluoride	< 10 ppb
Oxygen (O_2),	H_2O	< 10 ppb
Carbon Dioxide (CO_2),	H_2O	< 10 ppb
Nitrous Oxide (N_2O)	H_2O	< 10 ppb
Carbon Monoxide (CO)	Metal Carbonyls: Fe, Ni	
Corrosives (HCl, HBr, Cl_2, SiH_2Cl_2, $SiHCl_3$, BCl_3)	H_2O in inert gas	< 1 ppb
	H_2O in HBr	< 100 ppb
	H_2O in HCl	< 100 ppb
	Volatile Metals* **	
	Mo	< 4 ppb
	Ti	< 13 ppb
	Fe(CO)5	< 50 ppb

Impurity removal depends on purifier material and incoming gas specification
*Refractories as TMDSO (Tetramethyldisiloxane)
**CO is removed efficiently by OMX & OMX-PlusTM media at low flow rates (recommend 1/10 of normal flow rate)
***Metals removed as measured on wafer via VPD-ICPMS:
Al, Ca, Cr, Fe, Mg, Ni, K, Na, Zn
Metals removal as demonstrated by intrinsic resistivity measurements on wafer grown by TCS:
Without MTX Purifier: <200 ohm-cm
With MTX Purifier: > 2500 ohm-cm and total metals on water <1E10 atoms/cm2

Analytical Characterization of NANOCHEM® NHX™ Purifier

Impurity/Matrix	Efficiency (ppb)	Challenge (ppm)
H_2O in Ar	<0.3 (D/L)	35
H_2O in NH_3	<45 (D/L)	1000
CO_2 in He	<11 (D/L)	500
CO_2 in NH_3	<11 (D/L)	25
GeH_4 in N_2	<0.1 (D/L)	2.5
SiH_4 in N_2	<0.1 (D/L)	2.5
Siloxanes in N_2	<0.1 (D/L)	(trace)
GeH_4 in NH_3	<0.5 (D/L)	1.0
SiH_4 in NH_3	<1 (D/L)	1.0
H_2S in He	<0.3 (D/L)	50
TEOS (siloxane) in NH_3	<40 (D/L)	640
O_2 in NH_3	<50 (D/L)	100

Purifier Models

	WK-70 WK-75	WK-300	WK-500	WK-700	WK-2500	WK-5000
Media bed volume	50 ml 55 ml	300 ml	500 ml	700 ml	2500 ml	5000 ml
Maximum flow rate (in nitrogen), slpm (NM_3/hr)	10 (0.6)	75 (4.5)	150 (9.0)	225 (13.5)	500 (30)	800 (48)
Pressure Drop at maximum flow rate (psi), tested in N2 at 90 psi inlet	< 1 (<0.007 MPa)	(<0.14 MPa) < 2	(<0.04 MPa) < 5	< 7 (<0.05 MPa)	< 5 (<0.04 MPa)	< 4 (<0.03 MPa)
Max permissible operating pressure, psi	1000 (7 MPa)	500 (3.5 MPa)	500 (3.5 MPa)	500 (3.5 MPa)	500 (3.5 MPa)	500 (3.5 MPa)
Connections: Male face seal	1/4”	1/4”	1/4”	1/4”	1/4” or 1/2”	1/2”

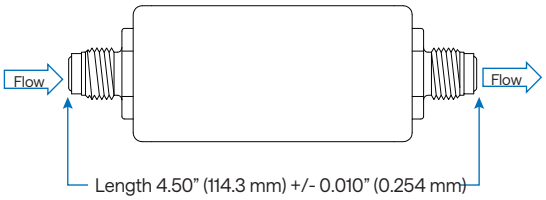
Specifications

- 0.003 µm filter (316L SS)
- Internal surface finish < 15 µin Ra
- Maximum operating temperature is 40°C

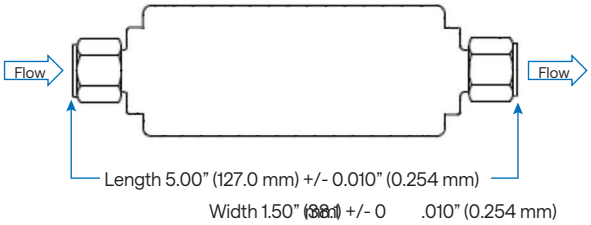
Options

- Inlet and outlet isolation valves
- Three-valve manifold with isolation and bypass valves allows disconnection of purifier without interrupting process gas flow for WK-75, WK-300, WK-500, WK-700, WK-2500 (1/4” and 1/2”) WK-5000.
- Poppet valves available for WK-75, WK-500, WK-2500

Dimensions

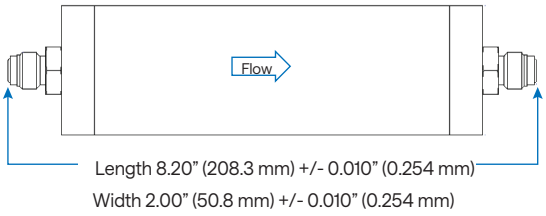


NANOCHEM® Purifier Model WK-70

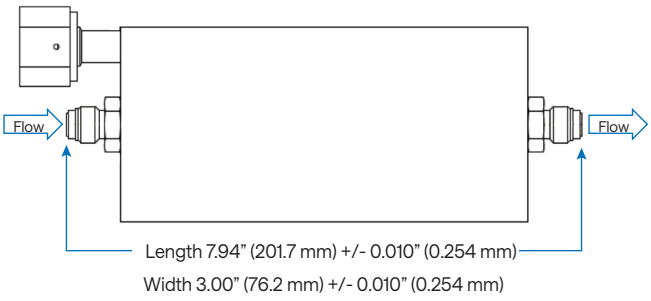


NANOCHEM® Purifier Model WK-75

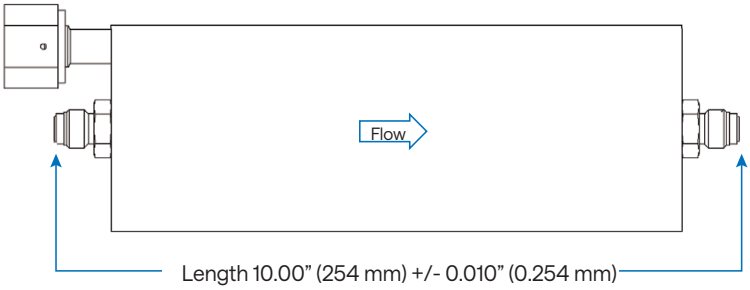
**actual media volume is 55 ml*



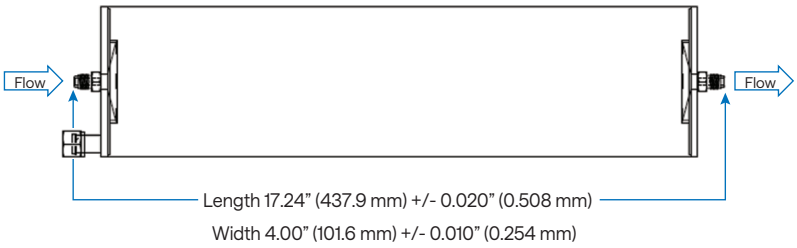
NANOCHEM® Purifier Model WK-300



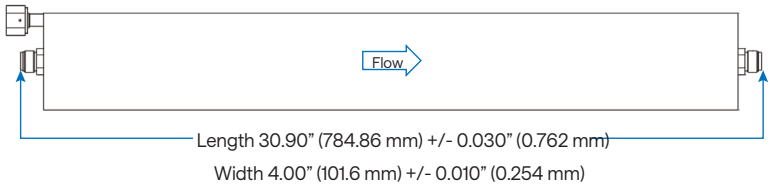
NANOCHEM® Purifier Model WK-500



NANOCHEM® Purifier Model WK-700



NANOCHEM® Purifier Model WK-2500



NANOCHEM® Purifier Model WK-5000

Dimensions in inches (mm)

Note: Purifiers are shown in horizontal position for illustration purposes only. Purifiers must be installed vertically.

Models WK-75, WK-300, WK-500, WK-700, WK-2500 and WK-5000 have a 0.003 µm particle filter.

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